



제25회 한국반도체학술대회

The 25th Korean Conference on Semiconductors

2018년 2월 5일(월)-7일(수), 강원도 하이원리조트 컨벤션 호텔

2018년 2월 7일(수), 09:00-10:30

Room H (청옥, 6층)

B. Patterning 분과

[WH1-B] 리소그래피 및 플라즈마에칭

좌장: 김현우 교수(한양대학교), 유원종 교수(성균관대학교)

<p>WH1-B-1 09:00-09:15</p>	<p>Analysis of Plasma Distribution Change by Edge Ring Height at a Wafer Edge Region In-won Park, Suk-Hyun Sung, Johnsoo Kim, Byung-Chae Park, Soeun Kim, Dohyung Kim, and Jong Chul Park <i>Process Development Team, Semiconductor R&D Center</i></p>
<p>WH1-B-2 09:15-09:30</p>	<p>N-type Doping Effects of Plasma Treatment on Surface Properties of Ultrathin Tungsten Diselenide Inyong Moon, Sungwon Lee, Kwangyoung Lee, and Won Jong Yoo <i>SAINT, Sungkyunkwan University</i></p>
<p>WH1-B-3 09:30-09:45</p>	<p>Effect of Plasma Treatment Using Oxygen and Nitrogen on Surface Properties of 2D Tungsten Diselenide Sungwon Lee, Inyong Moon, and Won Jong Yoo <i>Department of Nano Science and Technology, SAINT, Sungkyunkwan University</i></p>
<p>WH1-B-4 09:45-10:00</p>	<p>Interferometer Non-linearity 개선을 통한 EUV Overlay 개선 Jinwoo Choi, Sarohan Park, and Changmoon Lim <i>Research & Development Division, SK Hynix</i></p>
<p>WH1-B-5 10:00-10:15</p>	<p>Thermal Property Analysis of EUV Pellicle Membrane Jung Hwan Kim¹, Yong Ju Jang², Seong Ju Wi¹, and Jinho Ahn^{1,2} ¹<i>Department of Material Science Engineering, Hanyang University,</i> ²<i>Department of Nanoscale Semiconductor Engineering, Hanyang University</i></p>
<p>WH1-B-6 10:15-10:30</p>	<p>Mask Dummy Pattern 삽입을 통한 CD Uniformity 개선 Sunkyo Kim, Yeongbae Ahn, Jaeseung Choi, Chanha Park, and Hyunjo Yang <i>R&D Division, SK Hynix</i></p>